

New Release

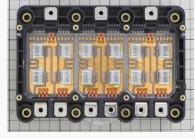
LTEC Corporation

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FUJI ELECTRIC '6MBI800XV-075V-01' IGBT MODULE FOR EV & HEV DETAILED ANALYSIS REPORTS

July 2019. LTEC Corporation released three reports (Module structure report, IGBT chip structure report & process flow and electrical characteristic report) of Fuji Electric IGBT module. This module is for automotive application, Vces=750V, Ic=800A. The IGBT chip is the 7th generation X series RC-IGBT (Reverse Conducting IGBT).





Module

Module inside

IGBT die image

Report contents

- (1) The module analysis report confirms the internal configuration of the module and reveals the layout of the RC-IGBT. In addition, we have clarified the structure and internal configuration of the cooler to estimate the heat removal mechanism.
- (2) The planar layout, cross section and EDX of RC-IGBT IGBT and FWD regions are included in the IGBT chip structure analysis report.
- (3) In the process analysis report, we consider the process technology of RC-IGBT, estimate the number of masks and the manufacturing process flow. The integration of the IGBT, the FWD and temperature sensors are revealed. We measure Ic-Vce characteristic, off-state collector leak current and breakdown voltage respectively, and extract the activation energy from temperature dependency of off-leak current. Furthermore the comparison with Infineon IGBT7 is also included.

Structure analysis report: (1)Module \$3,500 / (2) IGBT chip \$5,800 (3) Process and electric characteristic analysis report: \$4,600

Contact LTEC Corporation for the current price as it decreases over time

19G-0004-1



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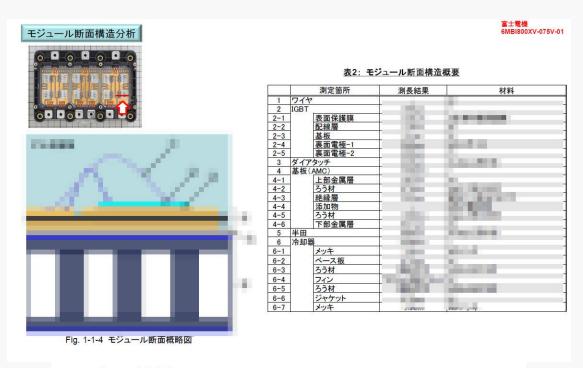


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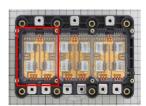
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Excerpts from the module structural analysis report (1)



3-1. モジュール内部観察



X方向寸法

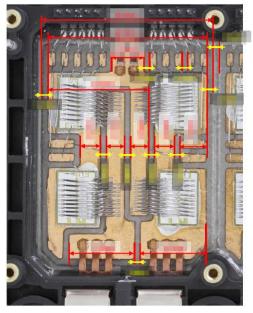
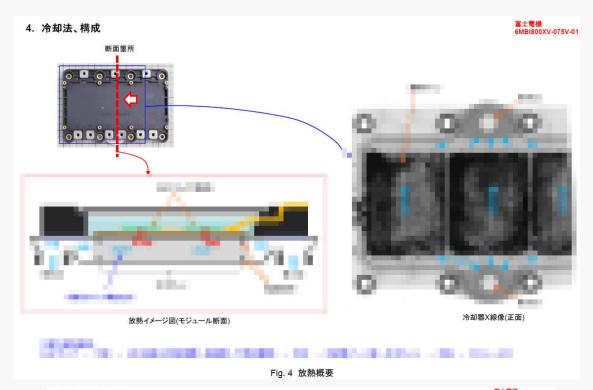


Fig. 3-1-6 モジュール内部拡大



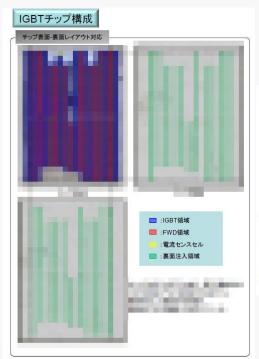
Excerpts from the module structural analysis report (2)

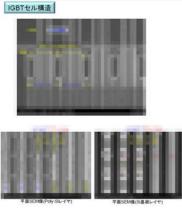


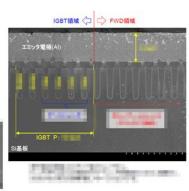


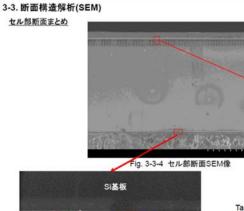


Excerpt from die structure analysis report

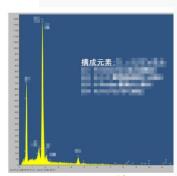












SEM-EDX結果

	SI基板
≫ B	裏面電極-1
×9	裏面電極-2
So to go	
1953	
	ダイアタッチ
0.00	

Fig. 3-3-5 裏面断面SEM像(IGBT/FWD境界)

	測定箇所	測長結果	材料
IGB		100	
	保護膜 ※	1000	A STREET, SQUARE, SQUA
120	表面電極	10000	100
	層間絶縁膜	100	10.00
3	コンタクトプラグ	10000	
	バリアメタル	100.000	
	Gate電極	186	PROJECT OF THE PARTY OF THE PAR
	Gate絶縁膜	100	100
7	基板	1800	-
3	裏面電極-1	100	W-11
9	裏面電極-2		



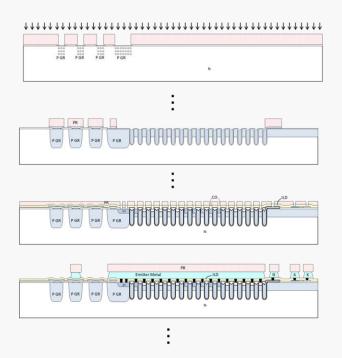
Excerpts from process and device characterization report



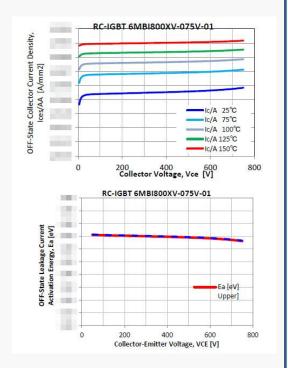
4-1. Si-RC-IGBTのフロントエンドウェーハプロセスフロー(推定)
マスク プロセス工程
ウスーハ Si-F2 N-Nype 基板 N-(~50-600cm) 新設化 粉板化上50mm

[1] AMフォト Alignment Mark

Wafer processing up to back-metallization: photo/masking steps ・チッププロセスレベル: 枚マスク(層)



Process flow sequence diagram



Off-state collector leakage current per unit area and extraction of the activation energy



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